## AMENDMENTS TO THE CLAIMS

**This listing of claims will replace all prior versions and listings of claims in the application:**

## LISTING OF CLAIMS:

1.     (canceled).

2.     (previously presented):  A method for wavefront measurement of an optical imaging system by means of a phase-shifting interferometry technique, the method comprising:

at least one of:

moving a phase-shifting structure and a detector element laterally relative to the optical imaging system to be measured, and

moving an object-side mask structure laterally relative to the detector element,

wherein a pupil image offset occurring owing to the relative lateral movement is taken into account by back calculating interferograms, wherein the interferograms are respectively recorded by the detector element, using a phase-shifting characteristic associated with the lateral movement, or

wherein the pupil image offset is taken into account by a computational correction of wavefront derivatives, obtained from the recorded interferograms, in the direction of lateral movement.

3.      (previously presented): The method according to Claim 2, wherein the

computational correction of wavefront derivatives in the direction of lateral movement is

performed using the relationship:

$$I^{(2)}(n) = \cos(S_x^{(1)} - \frac{\partial S_x^{(1)}}{\partial x} \frac{\Delta x(n-1)}{N} + \frac{2\pi(n-1)}{N}) \quad,$$

which specifies the intensity values $I^{(2)}$ of individual detector element pixels as a function

of the nth lateral phase shift with $S_x^{(1)}$ as errored wavefront derivative in the phase-shifting

direction, from which an error-corrected wavefront derivative $(S_x^{(2)})$ is then calculated, wherein

$N$ denotes a total number of phase steps.

4.      (currently amended): The method according to Claim 2, carried out with aid of a

device according to Claim 1 comprising:

a mask structure which is arranged on an object side, and

a grating structure which is arranged on an image side,

wherein the mask structure which is arranged on the object side comprises one or more

mask structure patterns with a periodicity in exactly one direction, and the grating structure to be

arranged on the image side comprises one or more grating structure patterns with a periodicity in

exactly two non-parallel directions, or

wherein the mask structure comprises one or more mask structure patterns with a

periodicity in exactly two non-parallel directions, and the grating structure comprises one or

more grating structure patterns with a periodicity in exactly one direction.

5.       (currently amended): The method according to Claim 3, carried out with aid of a device ~~according to Claim 1~~ comprising:

a mask structure which is arranged on an object side, and

a grating structure which is arranged on an image side,

wherein the mask structure which is arranged on the object side comprises one or more mask structure patterns with a periodicity in exactly one direction, and the grating structure to be arranged on the image side comprises one or more grating structure patterns with a periodicity in exactly two non-parallel directions, or

wherein the mask structure comprises one or more mask structure patterns with a periodicity in exactly two non-parallel directions, and the grating structure comprises one or more grating structure patterns with a periodicity in exactly one direction.

6.       (canceled).